

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S27	288	(photomask) and sputter\$5	JPO	OR	ON	2006/02/02 09:04
S28	9	(photomask) and sputter\$5 and rotat\$5	JPO	OR	ON	2006/02/02 08:37
S29	985	(photomask) and sputter\$5 and rotat\$5	USPAT	OR	ON	2006/02/02 08:42
S30	444	(photomask) and sputter\$5 and rotat\$5 and (target or cathode)	USPAT	OR	ON	2006/02/02 08:40
S31	105	(photomask) and sputter\$5 and rotat\$5 and (target or cathode) and offset	USPAT	OR	ON	2006/02/02 08:40
S32	1	(photomask) and sputter\$5 and rotat\$5	EPO; IBM_TDB	OR	ON	2006/02/02 08:43
S33	3	(photomask) and sputter\$5 and rotat\$5	DERWENT	OR	ON	2006/02/02 08:55
S34	6	(photomask) and sputter\$5	EPO	OR	ON	2006/02/02 09:05
S35	176	(photomask) and sputter\$5	DERWENT	OR	ON	2006/02/02 09:11
S36	0	rotat\$5 and "5981109".pn.	USPAT	OR	ON	2006/02/02 09:12
S37	1	"6756160".pn.	USPAT	OR	OFF	2006/02/02 09:18
S38	4	("20020119378" "4890309" "5897977" "6335124").PN.	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/02 09:24
S40	742	photomask and sputter\$5 and (rotat\$5 same (substrate or workpiece))	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/02 09:36
S41	619	photomask and sputter\$5 and (rotat\$5 same (substrate or workpiece)) and (source or target or cathode)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/02 09:27
S42	619	photomask and sputter\$5 and (rotat\$5 same (substrate or workpiece)) and (source or target or cathode)	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/02 09:27
S43	0	(Phase adj shifting adj blank) and sputter\$5 and ((rotate or rotating or rotated) same (substrate or workpiece))	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/02 09:36
S44	114	(blank\$2) and (phase adj shift\$5) and sputter\$5 and ((rotate or rotating or rotated) same (substrate or workpiece))	US-PGPUB; USPAT; USOCR	OR	OFF	2006/02/02 09:46
S45	1	JP-07140635-\$.did.	JPO	OR	OFF	2006/02/02 09:43
S46	1	(blank\$2) and (phase adj shift\$5) and sputter\$5 and ((rotate or rotating or rotated) same (substrate or workpiece))	EPO; JPO	OR	OFF	2006/02/02 09:46

S47	0	(blank\$2) and (phase adj shift\$5) and sputter\$5 and ((rotate or rotating or rotated) same (substrate or workpiece))	DERWENT	OR	OFF	2006/02/02 09:46
S48	60	(blank\$2) and (phase adj shift\$5) and sputter\$5	EPO; JPO	OR	OFF	2006/02/02 09:49
S49	74	(phase adj shift\$5) and sputter\$5 and mask	JPO	OR	OFF	2006/02/02 09:50
S50	73	(phase adj shift\$5) and sputter\$5 and mask	DERWENT	OR	OFF	2006/02/02 09:57
S51	2	("6286452" "6475354").PN.	USPAT	OR	OFF	2006/02/02 09:58
S52	1	("6086728").PN.	USPAT	OR	OFF	2006/02/02 09:59
S53	1	"20020106830"	US-PGPUB	OR	OFF	2006/02/02 10:04
S54	7	(photomask) and rotat\$5 and (substrate or workpiece) and deposit\$5	JPO	OR	OFF	2006/02/02 10:05
S55	3	(photomask) and rotat\$5 and (substrate or workpiece) and deposit\$5	DERWENT	OR	OFF	2006/02/02 10:06
S57	798	(photomask) and rotat\$5 and (substrate or workpiece) and deposit\$5 and sputter\$5	USPAT	OR	OFF	2006/02/02 10:06
S59	317	(photomask) and (rotat\$5 same (substrate or workpiece)) and deposit\$5 and sputter\$5 and (target\$2 or source\$2 or cathode\$5)	USPAT	OR	OFF	2006/02/02 10:10
S60	36	204/298.28.ccls.	JPO	OR	OFF	2006/02/02 10:12
S61	13	"204"/\$.ccls. and photomask	JPO	OR	OFF	2006/02/02 10:13
S62	45	204/298.26.ccls.	EPO; JPO; DERWENT	OR	OFF	2006/02/02 10:16
S63	37	204/298.28.ccls.	EPO; JPO; DERWENT	OR	OFF	2006/02/02 10:18
S64	40	204/298.18.ccls.	EPO; JPO; DERWENT	OR	OFF	2006/02/02 10:20
S65	67	204/298.18.ccls. and (rotat\$5 same (substrate or workpiece))	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/02 10:31
S66	2	"5995223".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/02 10:32

S67	2	"5955223".pn.	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/02 10:34
S68	0	"5955223".pn. and halftone	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/02 10:33
S69	0	"5955223".pn. and (half adj tone)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/02 10:33
S70	2	(halftone adj phase adj shift adj blank) and sputter\$5	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT	OR	OFF	2006/02/02 10:47
S71	0	targets and sputter\$5 and photomask and blank and (silicon or si)	DERWENT	OR	OFF	2006/02/02 10:48
S72	0	targets and sputter\$5 and photomask and blank and (silicon or si)	JPO	OR	OFF	2006/02/02 10:48
S73	33	targets and sputter\$5 and photomask and blank and (silicon or si)	USPAT	OR	OFF	2006/02/02 10:48